

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
ASMMC.033AUSAPPLICATION NO.
10/007,304INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Kim et al.FILING DATE
December 5, 2001GROUP
2812

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
SN	1	5,892,254	04/06/99	Park et al.			
SL	2	6,126,806	10/03/00	Uzoh			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
SL	3	WO 00/75964 A2	12/14/00	PCT				
SL	4	63299250	12/06/88	Japanese Patent Abstract			X	
SL	5	11111919	04/23/99	Japanese Patent Abstract			X	

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
SL	6	Gong et al., "Interdiffusion and reaction in the Cu/TiN/Si thin film system," Applied Surface Science, Vol. 92, pp. 335-339, (Dec. 1994)						
SL	7	Rha et al., "Improved TiN film as a diffusion barrier between copper and silicon," Thin Solid Films, Vol. 320, pp. 134-140, (May 4, 1998)						

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011503

EXAMINER

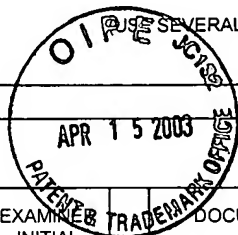
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FILING DATE
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6,271,592 B1

8/7/01

Kim et al.

EXAMINER
INITIAL

DOCUMENT NUMBER

DATE _____

COUNTRY

CLASS

SUBCLASS

TRANSLATION

YES

NO

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

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